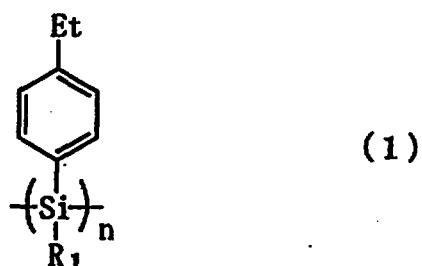
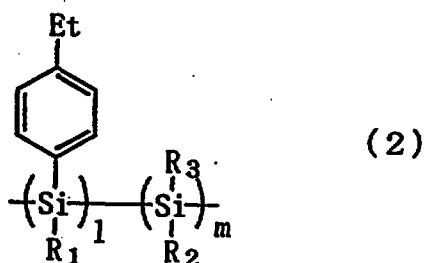


ABSTRACT

This invention provides a hole transporting material which has a structure represented by the following formula (1) or formula (2) and which is excellent in film-forming property and hole transporting characteristic



wherein R_1 is hydrogen atom and alkyl group, R_1 may be the same or at least two of them may be different from each other and n is in the range of 10 to 20000,



wherein R_1 is hydrogen atom and alkyl group, R_2 and R_3 are hydrogen atom, alkyl group, aryl group, alkoxy group, amino group and silyl group, R_1 , R_2 and R_3 may be the same or at least two of them may be different from each other, 1 is a positive number, m is zero or a positive number, and $1+m$ is in the range of 10 to 20000.